Amendments to the Claims

This listing of claims will replace all prior versions, and listings of claims in the application.

Listing of Claims:

1-14. (Cancelled).

15. (Currently amended) A chemical vapor deposition apparatus comprising:

a load-lock chamber;

a processing chamber mounted on said load-lock chamber;

a vent-line connected with said-load-lock chamber; and

an air purge line connected with said load-lock chamber, wherein said air purge line supplies the load-lock chamber with air including H₂O gas; and,

a vacuum pump connected to the air purge line and adapted to exhaust the residual gases from the load-lock chamber.

16. (Currently amended) The apparatus as recited in claim 15, wherein said air purge line and said vent line are connected to each other <u>further</u> comprising:

a vent line connected to the load-lock chamber and adapted to provide an inert gas to the load-lock chamber.

- 17. (Currently amended) The apparatus as recited in claim 16, further comprising a vacuum pump connected to wherein said vent line is connected to said vacuum pump.
- 18. (Currently amended) The apparatus as recited in claim $\frac{15}{17}$, further comprising an O_2 gas line connected to said air purge line.
- 19. (Currently amended) The apparatus as recited in claim 15 18, further comprising a filter connected to said air purge line.
 - 20. (Cancelled)
- 21. (New) The apparatus as recited in claim 18, wherein the O_2 gas line is connected to the vacuum pump.
- 22. (New) The apparatus as recited in claim 18, further comprising mass flow controllers connected to the air purge line, the vent line and the O_2 gas line so as to regulate flows and amounts of the air including H_2O , the inert gas and O_2 gas, respectively.